

Oxford Instruments Severn Beach: Driving advances in compound semiconductors

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Richard Tyson, CEO Matt Kelly, Managing Director, Plasma Technology



An introduction to a **world-class facility set** to address **structural growth** in the **compound semiconductor** market

What we'll cover today:

- Introduction Richard Tyson, CEO
- Compound semiconductor: the opportunity Matt Kelly, Managing Director, Plasma Technology
- Your questions
- Lunch
- Site tour and demonstrations



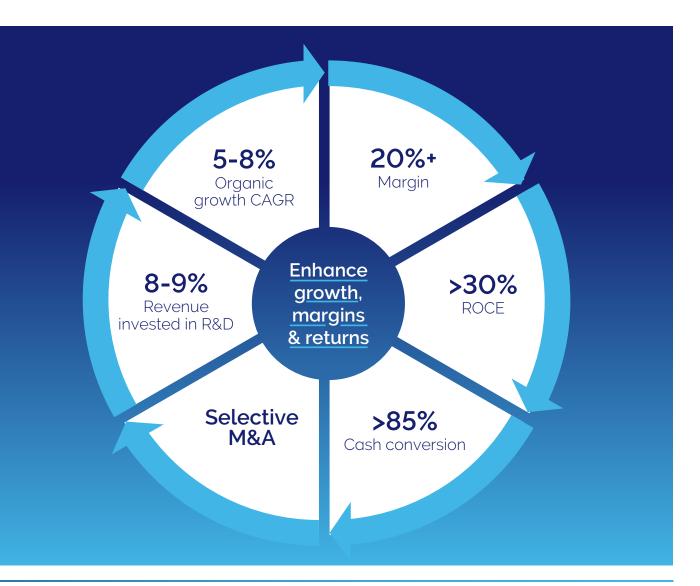
	Imaging & A Good to g	-	Advanced Technologies Fix, improve and grow		
Capabilities	Leading range of microscop spectroscopy and associated an	· ·	Compound semiconductor fabrication equipment Cryogenic and magnet technology for quantum and advanced materials research		
The opportunity*	Current c.£328m revenue 22-24% AOP margin recent history	Medium-term 23-25% AOP margin*	Current c.£142m revenue O-4% AOP margin recent history	Medium-term 10–12% AOP margin*	
The plan	 Excellent business and good track Share best practice across business Standardise processes Improve operating efficiency 		 Focus business on critical actions Extract full growth and margin potential from compound semiconductor and new facility Fix and improve Quantum business Improve operational performance and efficiency 		



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- New simplified divisional structure
- Three main markets: materials analysis, semiconductors and healthcare & life science
- Major operational improvement programme
- Step change in our customer performance
- Continue significant investment
 in technology





Three key structural growth end markets

Materials Analysis	4–7% Market growth pa*	£1.2bn Market size*	43% % Group revenue	 Structural drivers Supports advanced material development and sustainability progress Improved performance from finite resources
Semiconductors	6–9% Market growth pa*	£1.5bn Market size*	27% % Group revenue	 Structural drivers Enabling development of new compound semiconductors Growth in bandwidth, connectivity and faster devices Power efficiency and green economy
Healthcare & Life Science	8–12% Market growth pa*	£2.0bn Market size*	19% % Group revenue	 Structural drivers Improved treatments & vaccines; reduced cost of development Personalised medicine & therapies Ageing population

* Market growth opportunities refer to applied R&D and production and testing; market size = our addressable market annually Source: SDi/Gartner

c.90% of Group revenues in <u>three key markets</u> exhibiting strong structural growth Other 10% includes quantum: uncertain timing and technology, high potential



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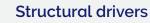
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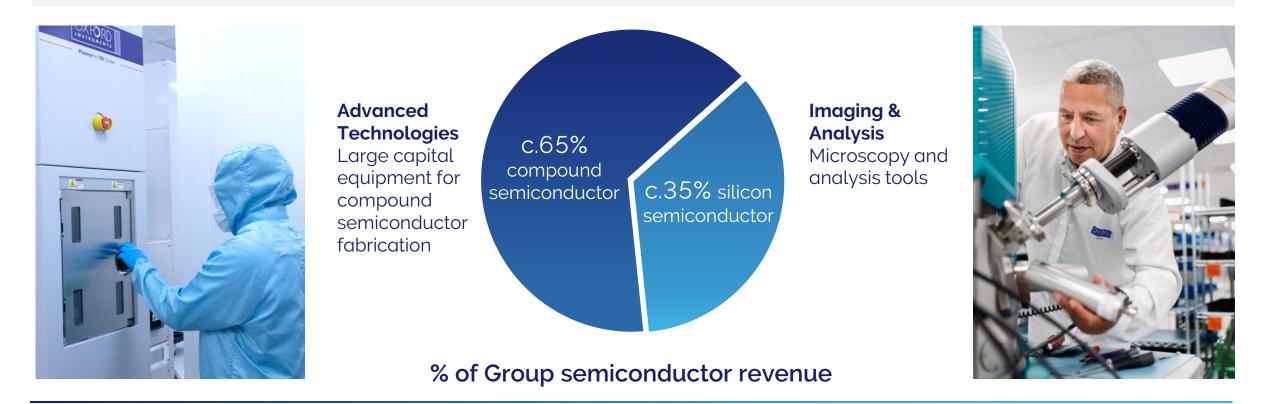




£1.5bn Market size*



- Enabling development of new compound semiconductors
- Growth in bandwidth, connectivity and faster devices
- Power efficiency and green economy

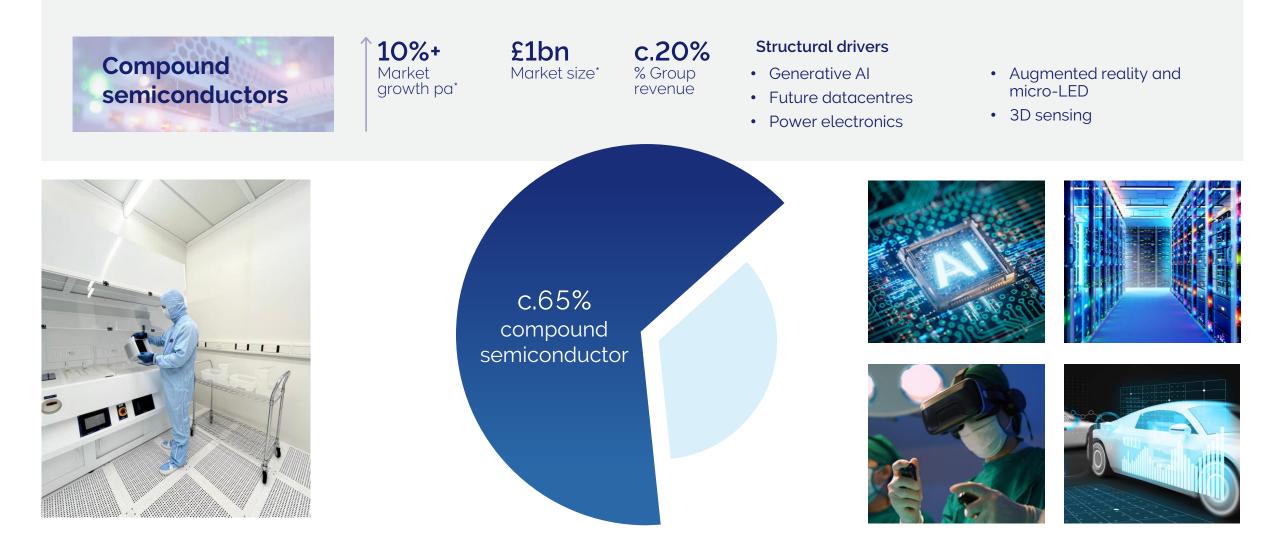


27%

% Group

revenue







Compound semiconductors: The opportunity

Matt Kelly, Managing Director, Plasma Technology





From a pioneer in a nascent field of technology to a global installed base and a world-class facility



Founded in 1980 to address the high-end plasma physics research market... acquired by Oxford Instruments in 1990









Business scales and transitions to attract both academic and commercial customers, reaching a global installed base of more than 3,500 systems



New worldclass facility opens at Severn Beach; business reaches £90m revenue

2024

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1980

The <u>efficiency</u> and <u>flexibility</u> of compound materials <u>enables applications not possible</u> with <u>silicon</u>

- Higher energy efficiency
- Higher power
- Wider temperature range
- Greater optoelectronic properties



Silicon carbide

More efficient power conversion in electric vehicles & renewable energy



Gallium nitride

5G/6G base stations, power-efficient consumer electronics and micro-LED display



Higher growth market with 10%+ CAGR

Gallium arsenide

3D sensing arrays and short-range fibre connections in datacentres



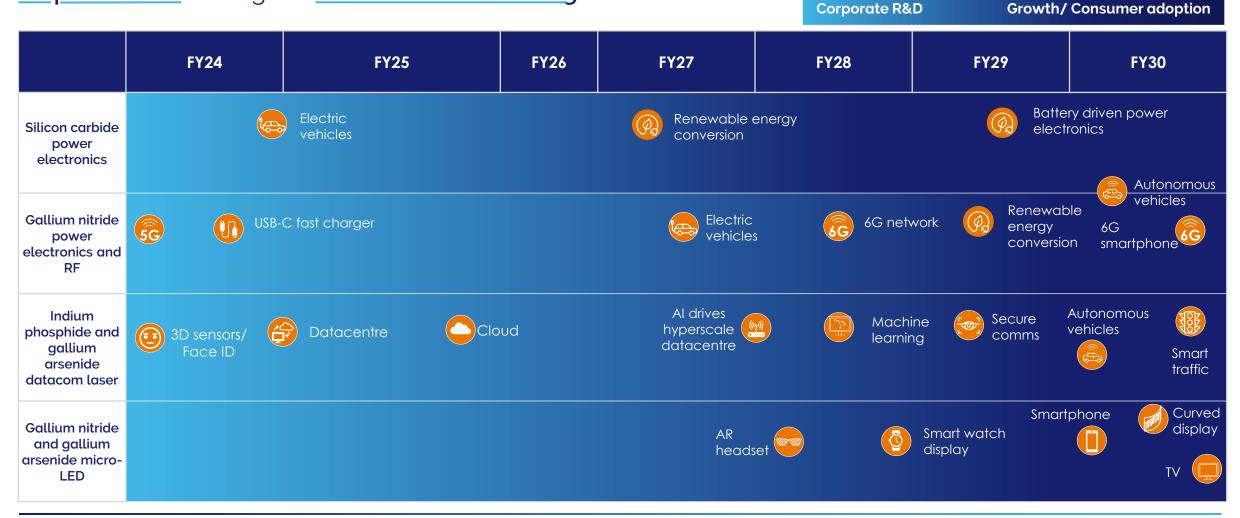
arsenide & gallium

Increased optical fibre data bandwidth for next gen lasers and receivers

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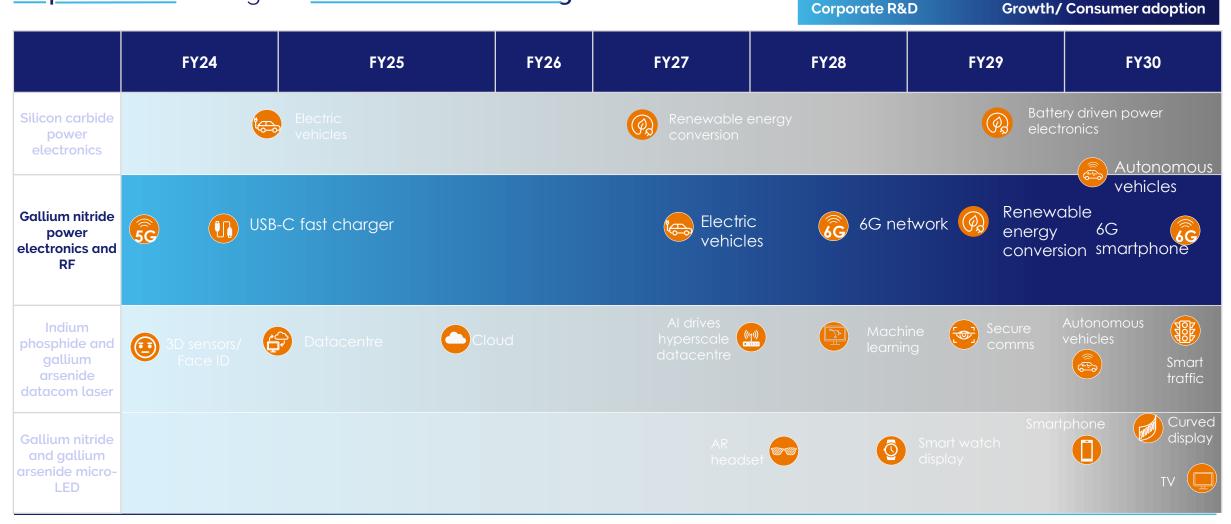


Plasma Technology involved from <u>early-stage research</u> and <u>corporate R&D</u> through to <u>volume manufacturing</u>





Plasma Technology involved from <u>early-stage research</u> and <u>corporate R&D</u> through to <u>volume manufacturing</u>





The journey to volume manufacturing: from niche to mainstream

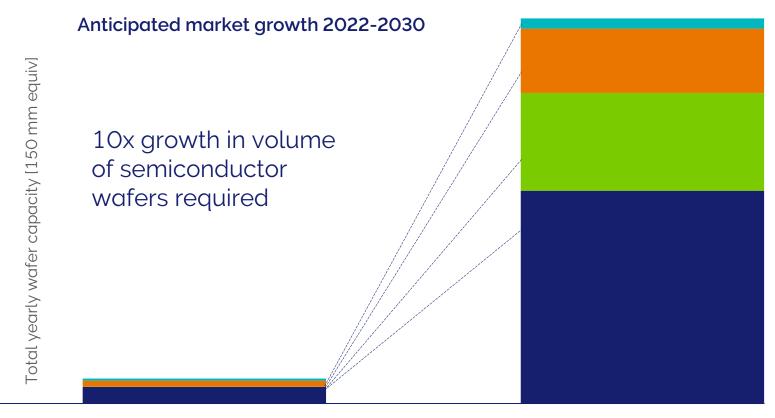
Plasma Technology scaling up in line with market growth in hardware, process and fab integration

Indium phosphide/ Gallium arsenide datacom laser

Silicon carbide power electronics

Gallium nitride and gallium arsenide Micro LED

Gallium nitride power electronics and RF



2022

The global landscape: investments into new chip technology



Governments globally committing to significant national programmes

Chart shows spending commitments with date announced



Americas USA: \$280 bn CHIPS Act (2022) Canada: \$240m (2022); \$60m (2024)

Compound markets are forecast to grow significantly, in particular outside China, driven by:

- Substantial volume of global funding, tax incentives offered by governments to drive catch up.
- Drive for localisation of supply chain to minimise exposure to regional risks
- Attractiveness of high margin 'technology-driven' applications.

EMEA EU: €43bn (2023 European Chips Act) Germany: €20bn (2023) Italy: €10bn (2024) Spain: €12bn (2022) UK: £200m (2023) **China** \$47.5bn (Phase 3: 2024)





Rest of South East Asia South Korea: \$19bn (2024) Singapore: \$18bn (2021-25) Malaysia: \$5.3bn (2024)

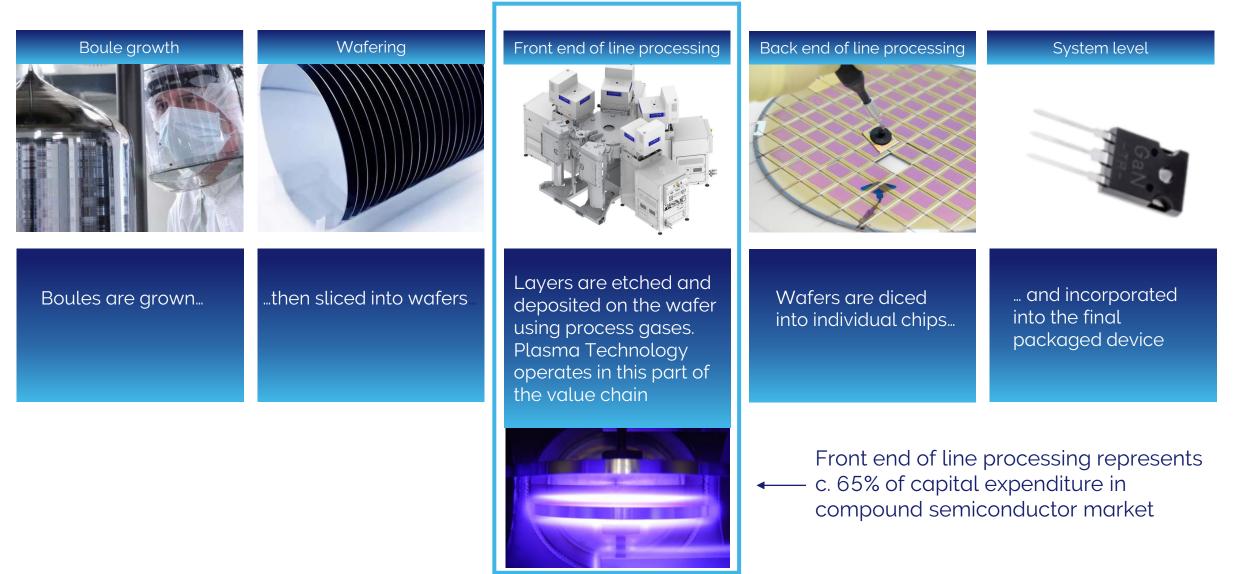
Gallium nitride power electronics & RF Silicon carbide power electronics

3D sensors and data communications

Augmented reality and micro-LED

Plasma Technology: playing a critical part in the compound semi value chain







Enabling increased bandwidth in data communications using indium phosphide



Strong footprint in an established market

Driving improved power efficiency with gallium nitride devices



Growing footprint in a <u>new market</u> Enabling advances in augmented reality and micro-LED using atomic layer etch and deposition



Strong potential in an **R&D phase technology**



Silicon carbide for power electronics



High thermal conductivity and maximum current density enable:

- Improved efficiency
- Smaller size
- Lower weight





EVs



Lower temperature

Faster switching

Disruptive <u>Plasma Polish</u> technique has potential to support <u>silicon carbide market</u> <u>scaling</u>, enabling volume production of more <u>high-quality wafers</u> at a <u>lower cost</u>



- Alternative to standard chemical polish process currently in advanced feasibility studies
- Removes surface damage
- Reduces polishing cost
- Reduces environmental impact



Why we win: superior technology and capabilities in carefully targeted and specialist growth markets

Charging nov

%50

- Vast amount of experience and know-how built up over 40 years
- Unique breadth of technology in our part of the value chain
- Unparalleled access to metrology as part of the wider Oxford Instruments offering

Enabling USB-C fast charging

A **\$35** reduction in wafer cost for a US customer

30% market

share achieved

in smartphone fast charging

Future GaN applications

Working with leader in automotive supply chain on 350 KWh+ EV chargers to reduce charging time:

30 mins to <10 mins

ROHM

Enabling our customers to achieve higher performance, better quality and a higher wafer yield at a lower cost









Legacy Yatton site: **no longer compatible** with customers' needs or the needs of the business

- Site has supported revenue growth from £10m to £70m, but layout not optimised and facility had reached end of life
- Credibility with large market players
 was compromised





New Severn Beach site reinforces right to play in volume production

Tripling potential capacity versus legacy site Application lab will accelerate R&D and validation capabilities Extensive customer suite facilitates on-site testing and collaboration World-class cleanroom to be operational Q4 24/25



2000-2010 Transactional relationship

2010-early 2020s Adding extra value

Today-2030 and beyond Fully integrated partner





Our **world-class clean room** and **applications lab and metrology capabilities** are the key to becoming **an indispensable partner** to our customers



Transition to value stream management	Standardised product range and removal of 'specials'	Moving people rather than equipment in build and test phase	
Visual management introduced	More modular design enables quality control and stronger supply chain integration	Team engagement and resourcing for future via introduction of talent academy	

Driving efficiency and lean principles



15% productivity improvement to date on Plasma Pro 100:

Production time reduced by 40 hours to 220 hours

Target: **180 hours**



Ramping up to maximise growth and address the needs of high-volume manufacturing



Focused segment team



Optimising our footprint in Japan and SE Asia

Total **pipeline** of opportunity for Plasma Technology **doubled** from **£250m to £500m** in last three years

infrastructure

Investment in

service

Channel partnerships

<u>c. 17%</u> Plasma Technology revenue generated from service today, with scope to grow to <u>20%</u> and beyond



Market & customer focus



Operational excellence



Capitalise on potential within our target markets moving from low volume to volume manufacturing Streamline R&D and manufacturing process towards operational excellence Extend uptime and develop enhanced service offerings

Value solution partner

Talent and culture



Developing the team and culture for the volume manufacturing journey



	Building on our growth track record			The journey to high-volume manufacturing		
The opportunity	Doubled revenues in the last 5 years	High single digit margins		Double revenues gain - compounding >10% growth	Medium term mid-teens+ margins	
The market	From a nascent market to coming of age Moving from academic to commercial applications		I	A high growth market with clear structural drivers Increasing adoption for diversified commercial applications		
Facilities	Capacity constrained, lower specification facilities Enabled a substantial installed base but didn't support volume production			Operational leverage thereaf	riple capacity for growth ter as we drive productivity and ciency	

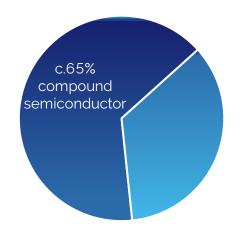


Well-positioned in the 10% + compound semiconductor growth market

A key enabler of next generation chips and market adoption

Competitive advantages enhanced by new world-class facility

A clear plan to grow both revenue and margin



% of Group semiconductor revenue (largest part of Advanced Technologies)

> 10% revenue CAGR

Mid-teens + Medium-term margin

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To accelerate the breakthroughs that create a brighter future for our world.

Our technology and scientific expertise enables our customers to discover and bring to market exciting new advances that drive human progress.



Appendix



Semiconductor

Generic name for transistors and integrated circuits that can control the flow of electric signals.

Transistor

Named for its electrical characteristic of "transfer resistance," these are the current switches that are the essential building blocks of integrated circuits.

Integrated device

Components in a circuit that combine to perform one or more functions (e.g. a laser with a transmitter and receiver)

Discrete device

A device that performs a single function found in electrical circuits (e.g. a high-voltage switch)

Die

One individual integrated chip built onto a wafer.

Diode

An electronic device that restricts current flow chiefly to one direction.

MicroLED (µLED)

A few micron-sized type of light emitting diode (LED) that are packed incredibly densely together into small high-definition screens (e.g. Apple watch)

Augmented (AR) or virtual (VR) reality

AR – technology that overlays images into the natural environment that the user is in. VR – an alternate computer-generated reality that the user enters using a headset that removes the sense of them still being in the natural environment



Fabrication

The process of creating devices, carried out in a fab, or many fabs.

Epitaxy

After substrate fabrication, the next step is often to deposit a layer of material (an epitaxy or 'epi' layer) with critical material properties that makes the device function as designed.

Passivation

A layer of insulating material deposited on a wafer to stabilize and protect the surface against moisture, contamination, and mechanical damage.

Dielectric

Dielectrics are layers used within the device to mask against the diffusion of dopants and provide tuneable electrical isolation between material layers

Doping

The combination of a chemical impurity into the crystal structure of a semiconductor to modify its electrical properties.

Lithography

The transfer of a pattern or image from mask to wafer; "photolithography" uses light to affect the transfer.



Deposition

The procedure in which films of insulating and/or conducting materials are deposited onto a wafer.

Etch

Chemically removing material from the wafer, sometime using a mask to selectively remove areas of material while leaving the rest untouched.

lon beam

Primarily a high physical and low chemical form of etch and deposition that allows material to be removed or added at angles to the surface of the wafer

ALD (Atomic Layer Deposition)

Thin films are grown in cycles where the surface is exposed to various gasphase species in alternating doses, and isolated by evacuation or inert purging. Only a single layer of precursor absorbs the surface.

ALE (Atomic Layer Etching)

A precise process that etches single atomic layers of a material, which ensures extremely low damage and high levels of accuracy.

PECVD (Plasma Enhanced Chemical Vapour Deposition)

Process of applying a thin film to a substrate using chemically reactive gasses and plasma.



Cleanroom

A low or dust free area to reduce contamination getting onto the wafer surface and into the devices

Cluster

An array of processing chambers around a single load lock chamber housing a substrate handling robot.

Load lock

A sealable chamber adjacent to the processing chamber, which allows the specimen to be loaded onto the substrate table without having to vent the processing chamber.

Boule and wafer (a.k.a substrate)

Boules are manufactured cylindrical crystal blocks that have been grown from materials like silicon, silicon carbide, gallium arsenide or indium phosphide. Boules are sliced horizontally to form crystal discs known as wafers or substrates, that are the starting material for devices to be fabricated on the surface

Substrate

The underlying material on which a microelectronic device is built.

Precursor

Chemical compound which reacts with a second reactant to form another related material.

Process gas

Specific types of gas that are fed into the chamber and ignited with radio frequency energy to create a bright chemically reactive plasma gas

Plasma

A mix of electrons, positive ions and neutral gas particles created between electrodes within which the various etching or deposition processes take place.

Silicon carbide

The main compound material for advanced power applications in the high voltage range.

Gallium nitride

The main compound material for advanced power applications in the low to medium (maybe high voltage in future) voltage range.

Gallium arsenide

The main compound material for creating the types of laser used in facial recognition and some short-range data transfer.

Indium phosphide

The main compound material for creating the types of laser used in longrange data transfer and long-distance environment sensing in automotive applications.

2D TMDs (Two-Dimensional Transition Metal Dichalcogenides)

Atomically thin semiconductors that intrinsically have a 2D nature. Their chemical formula is written as MX₂, where M is a transition metal (such as Molybdenum or Tungsten), and X is a chalcogen (such as Sulphur or Selenium).

Band gap and wide band gap (WBG)

In electronics, electrons in atoms are manipulated to move from their default valance band to the conduction band, to make the materials do something useful in the circuit like emit light or act as a switch. Materials with electrons that are easily manipulated to move, like silicon, are narrow band gap, and advanced materials such as silicon carbide and gallium nitride, have a wide band gap. Wide band gap materials are harder to produce, but are much more efficient, effective and ideally suited to advanced electronic devices.